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Atty Docket No.	Application No.
112857-307	10/024,883
Applicant	
	uki Okuyama et al.
Filing Date	Group
12-17-2001	2823

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U.S. PATENT DOCUMENTS						
Examiner's Initials	Document Number	Publication Date	Inventor	Class	Subclass	Filing Date If Appropriate

			ENT DOCUMEN	NTS			
Examiner's	Document	Publication				Trans	
Initials	Number	Date	Country	Class	Subclass	Yes	No
9/8	56-92577	07-27-81	Japan	×.	ン		*
908	57-45583	03-15-82	Japan				×
WB	57-52071	03-27-82	Japan				V
WB	57-52072	03-27-82	Japan				/
9VB	57-52073	03-27-82	Japan				/
918	58-50577	03-25-83	Japan				V
WB	61-156780	07-16-86	Japan				/
and.	63-188938	08-04-88	Japan			ABS	
m.B	02-263668	10-26-90	Japan			Acs	
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9/8	07-199829	04-08-95	Japan			AB5	-
9/B	08-008217	01-12-96	Japan			ABS	-
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a/8	09-129974	05-16-97	Japan			AB5	
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av B	WO 97/44612	11-27-97	PCT			AB5	-
WB	10-125929	05-15-98	Japan			ABS	
av B	10-265297	10-06-98	Japan	×	×	AB	

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Applicant Hiroyuki Okuyama et al.

Filing Date Group 2823

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Initials	Number	Date	Country	Class	Subclass	Yes	No
9VB	10-270801	10-09-98	Japan	8	×	ABS	
900	10-312971	11-24-98	Japan	(ABS	
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9/13	11-346004	12-14-99	Japan	1)		数タム	. 7
9VB	2000-012976	01-14-00	Japan			A. 5.5	
WB	2000-068593	03-03-00	Japan			ARS	2 2 3
WB	2000-150391	05-30-00	Japan			A#S	<u> </u>
9VB	2000-183451	06-30-00	Japan			ASS S	
9/13	2000-223417	08-11-00	Japan			AB5	
9VB	2000-332343	11-30-00	Japan		1	ABS	-
WB	2001-085738	03-30-01	Japan)	ABS	
GNB	2001-217503	08-10-01	Japan		1	ABS	
908	2002-185660	12-12-02	Japan	X	X	ABS	$\neg \neg$

Examiner's Initials	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)
g/B	Zheleva et al., Pendeo-epitaxy – a new approach for lateral growth of gallium nitride structures, MRS Internet J. Nitride Semicond. Res. 4S1, G3.38 (1999).

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Examiner's Initials	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)
A/B	Kapolnek et al., Spatial control of InGaN luminescence by MOCVD selective epitaxy, Journal of Crystal Growth, 189/190 (1998) pp. 83-86.
9113	J. Wang et al., Fabrication of nanoscale structures of InGaN by MOCVD lateral overgrowth, Journal of Crystal Growth 197 (1999), pp. 48-53.
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WB	Tachibani et al, Selective growth of InGaN quantum dot structures and their microphotoluminescence at room temperature, Applied Physics Letters, Vol. 76, No. 22, May 29, 2000, pp. 3212-3214.
900	Yang et al., Single-crystal GaN pyramids grown on (1 1 1)Si substrates by selective lateral overgrowth, Journal of Crystal Growth, Volume 204, (1999), pp. 247-418.

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